Challenges in Experimental Surface Analysis of Plasma-Facing Materials

Bruce E. Koel

Department of Chemical and Biological Engineering, Princeton University NSTX Collaborator, Princeton Plasma Physics Laboratory (PPPL)

> BPSFG, PPPL June 29, 2011





Plasma Facing Materials for Fusion

(1) National Spherical Torus Experiment - NSTX

M Ulrickson

The Central Issue: How to interface a 100 million degree burning plasma to its room temperature surroundings?

Magnetic topology 'diverts' most PMI away from plasma to minimize plasma contamination but also concentrates heat load in space.

Low plasma density and size limitations lead to high edge gradients and repetitive relaxations or 'ELMS' that concentrate heat load in time as well !



REGION



2

Surface Interactions at the Plasma-Materials Interface



Whyte and Wirth, unpublished



Surface Science in the Koel group

New insights and materials from studies of structure and reactions at interfaces

Selective hydrogenation catalysis: Controlling selectivity in reactions over Sn-Pt surface alloys

Oxide nanostructures: Properties and reactivity of SnO₂ films and nanocrystals

Alloy electrodes: Novel Au-Pd₃Fe(111) alloys for oxygen reduction in PEM fuel cells

Liquid-solid interfaces: Development of Rutherford backscattering as a probe for nanometer characterization of electrodes in solution under potential control

Metal sorption on Fe nanoparticles: As sequestration by iron np for environmental remediation





1330 1328 1326 1324 1322 1320 Binding Energy (eV)



Surface Science of Materials Challenges for PMI

Liquid metal surfaces

- Li, Ga, Sn, Li-Sn eutectics
- Segregation in binary and ternary alloys
- Chemical reactions on alloy surfaces

Solid-solid and solid-liquid interfaces

-Metal-metal and metal-oxide adhesion energies

–Influence of surface nanostructure, grain size, morphology, native and applied coatings

Plasma processing of materials

-Ion-surface scattering, implantation, sputtering

-Radical-surface interactions (D chemistry)

-Electron-stimulated processes



Surface Science - Methodology

Surface Analytical Methods

- ✓ AES (Auger electron spectrosco)
- ✓ SAM (Scanning Auger electron r
- ✓ LEED (Low energy electron diffra
- ✓ RHEED (Reflection high energy)
- ✓ XPS (X-ray photoelectron spectr
- ✓ XPD (X-ray photoelectron diffrac
- ✓ LEIS (Low energy ion scattering)
- ✓ ALISS (Alkali ion scattering) —
- ✓ RBS (Rutherford backscattering
- ✓ HREELS (High-resolution electro
- ✓ FTIR (Fourier transform infrared
- ✓ TPD (Temperature-programmec
- STM (Scanning tunneling micros
 Approach



- Well-defined single crystals and thin films formed by vapor deposition
- Composition and structure, thermal and chemical transformations
- Reaction mechanisms, intermediates, and *reactive-sites*

Nucleation, growth, and alloying of Ge films on Pt

Ge on Pt(111)

Ge on Pt(100)





Co-existence of Ag-Pt alloy and pure-Pt hex domains



$(150 \text{ nm})^2$

Ag-Pt-alloy phases appear darker, distinguished from pure-Pt hex phases for 0.25-ML Ag on Pt(100) after annealing to 900 K



$(75 \text{ nm})^2$

Single-unit-cell-wide Pt(100)-hex domains surrounded by Ag-Pt alloy phase in thermodynamic equilibrium



Site-directed chemistry: 3-fold Pt sites on PtSn alloys yield benzene





Cyclohexane conversion probed by cyclohexyl radicals from electroninduced dissociation (EID)

Ch. 2 "Structure, Characterization and Reactivity of Pt-Alloy Surfaces", B. E. Koel, in *Model Systems in Catalysis: From Single Crystals and Size Selected Clusters to Supported Enzyme Mimics,* R. M. Rioux (Ed.), (Springer, 2010), pp. 29-50.

Sn-adatoms are more effective than alloyed-Sn in blocking sites



Sn/Pt(100)





10

Improving the O_2 reduction reaction rate in fuel cells using novel alloy electrodes





Powering Life.™

Electrode Reaction of Li / SVO Battery

- Cathode half reaction
 - Silver reduction $Ag_2V_4O_{11} + 2Li^+ + 2e^- \rightarrow Li_2V_4O_{11} + 2Ag$
 - Vanadium reduction $Li_2V_4O_{11} + 5Li^+ + 5e^- \rightarrow Li_7V_4O_{11}$
- Anode half reaction

 Lithium oxidation
 Li → Li⁺ + e⁻
- Full cell reaction $Ag_2V_4O_{11} + 7Li \rightarrow Li_7V_4O_{11} + 2Ag$



XPS/XPD/LEIS/ALISS instrument



Resistive heating of Li in crucible or SAES getter source

• Li film growth

Deposition of submonolayer or thicker Li films om vacuum or reactive gas environments and heat substrate to high temperature



Low Energy Ion Scattering (LEIS or ISS)





Elemental composition of ONLY the top-most atomic layer

Desorption of Adsorbed Carbon on Mo(100) by Noble Gas Ion Sputtering: Validation of Ground Test Measurements of Ion Engine Lifetime





Sputtering of adsorbed carbon is important in surface cleaning and in ground testing of ion thruster lifetimes

Ion sputtering desorption cross section is used to characterize how efficiently surface atoms are removed

Does carbon deposited during ground testing artificially reduce the Mo grid sputtering rates and thus increase estimates of grid lifetime?

Desorption for C on Mo(100) increase with mass of impinging ion

- C desorption maximum at an incident angle of 30°
- C desorption maximum at 300°C
- C desorption increases with ion energy

Deposited carbon does not reduce Mo grid erosion rate during ground testing. The measured lifetime can be used with confidence in predicting engine wear in space.









Surface vibrations from HREELS



Multichannel Electron Energy Analyzer (Model ELS5000 MCA)

High Resolution Electron Energy Loss Spectroscopy (HREELS)





HREELS instrument



⁷ Princeton Surface Science

Structure-reactivity relationships for tin oxide thin films



Incommensurate SnO_x monolayer

STM



(5x5) SnO_x monolayer



(4x4) SnO₂ multilayer

Batzill, et al., Phys. Rev. B, 69, 165403 (2004)



Electronic and vibrational properties of SnO_x films



HPPES: In-situ reactivity of SnO_x films at 10 Torr





Less reactive than the (4x4) monolayer: 2.2 Torr H_2 , 450 K, 5 min

SAM imaging of polycrystalline surfaces and segregation



Scanning Auger Electron Microscopy (SAM)

VG-Scientific Microlab 310F with AES, SAM, SEM, XPS

SEM picture of the intercrystalline surface of a Fe-Si-Sn alloy, fractured in UHV



SAM picture of the surface of steel containing 0.05 % Sb steel, showing how segregation depends on grain orientation www.imt.si



22







hom ,

800

Scanning tunneling microscopy (STM)



XPS controlled laboratory studies





Restaur



After cleaning procedures (sputtering, annealing), post mortem tiles exhibit peaks resembling those of offline, controlled experiments.



JP, CT - Purdue

PURDUE

Temperature Programmed Desorption (TPD)

Temperature Programmed Desorption (TPD)

- Heat sample while detecting the evolved gas using a mass spectrometer.
 - As temperature increases species desorb and are detected as an increase in pressure
 - Temperature of peak maximum provides information on the binding energy of the desorbing species

Measure and calculate I i adhesion energy from TPD, e.g. Li on Mo



Rate

Li/Si(100)

m/e=7

θLi (ML)

5.0 4.0

3.0 2.5 2.0 1.5

1.25

1.0 0.75

0.5 0.25

800



H atom - Surface Chemistry

Semiconductors

- Silicon
 - 1. Boland, J.J., Surf. Sci., 261, 17, (1992)
 - stability of 3 phases of hydrogenated Si(100) to addition of H atoms correlates inversely to the bond strain
 - 2. Koleske, D.D., Gates, S.M., Schultz, J.A., J. Chem. Phys., 99(7), 5619, (1993)
 - H abstracts D adsorbed on Si(100) with an $E_a=0.8$ kcal/mol
- Gallium Arsenide
 - 1. Creighton, J.R., *JVSTA*, 8(6), 3984, (1990)
 - H etches GaAs(100); prefers As and abstracts up to 15% of the surface arsenic
 - 2. Qi, H.; Gee, P.E.; Nguyen, T.; Hicks, R.F.
 - sticking coeff = 0.1 to 1.0 from 303 to 433 K on GaAs(100)
- Misc
 - Chang, R.P.H.; Chang, C.C.; Darack, S.
 - Selective etching rates for H plasmas: Si/SiO₂=30, GaAsO/GaAs=2; In/P(in InP)<1

Metal Single Crystals

- Copper
 - 1. Sandl, P; Bischler, U.; Bertel, E.
 - S=.18 on Cu(110); subsurface adsorption possible
- Nickel
 - 1. Bischler, U.; Bertel, E.
 - One dimensional chain reconstructions observed on Ni(110)
 - 2. Johnson, A.D.; Maynard, K.J.; Daley, S.P; Yang, Q.Y.; Ceyer, S.T.
 - H atoms have S=0.05 into the bulk of Ni(111)



H Atom Chemistry with Atomic and Molecular Adsorbates

Eley Rideal mechanisms observed for several reactions

Atomic Adsorbates

- Chlorine
 - 1. Zhou, X.L.; White, J.M.; Koel, B.E. Surf. Sci., 218, 201, (1989)
 - Cl blocks the adsorption of H on Ag(111)
 - 2. Jackson, B.; Persson, M.; Kay, B.D. J. Chem. Phys., 100, 7687, (1994)
 - H(g)+ Cl(a)/Au(111) is shown to have a very small (few%) probability of forming HCl
- Oxygen
 - 1. Xie, J.; Mitchell, W.J.; Lyons, K.J.; Wang, Y.; Weinberg, W.H. JVSTA, 12(4), 2210, (1994)
 - up to 50% of the surface O can be removed as water from Ru(100)-p(1x2)-O
- Carbon
 - 1. Biener, J.; Schenk, A.; Winter, B.; Lutterloh, C.; Schubert, U.A.; Kuppers, J. Surf. Sci., 307-309, 228, (1994)
 - chemical erosion of graphite by H

Molecular Adsorbates

- n-butane
 - Nicholas, J.E.; Vaghjiani, G.L. J.Chem.Phys., 91, 5121, (1989)
 - calculates graph of reaction cross section of H+ n butane.
- ethylene, benzene
 - Xi, M.; Bent, B.E. *JVSTB*, 10, 2440, (1992)
 - cross sections: 18 A² for D/ethylene; 15 A² for D/benzene



Design of clean H atom doser



J. Phys. Chem. 92 (1988) 2862



1200

UHV-compatible Plasma Source: tectra microwave/ECR atom, ion and atom/ion hybrid source

Atom source

Atom flux: >2x1016 atoms/cm2/s at 10cm Nitrogen, Oxygen, Hydrogen (any most other non-condensible gases) Working pressure: 1x10-8 mbar

lon source

Ion current density: >2mA/cm2 at 1.3keV and >0.05mA/cm2 at <100eV at 120mm distance Ion energy: 25eV - 2000eV



R.Anton, T. Wiegner, W. Naumann, M. Liebmann, C. Klein, C. Bradley, Rev. Sci. Instr. Feb 2000



Liquid Metals of Interest: Li, Ga, Sn

```
Alloys Studied: Li-Al, Li-Cu, Li-Sn
```

Fundamental Questions: What is the composition of the Liquid Surface? (as most of the sputtered erosion originates at the surface).

Atoms with lower surface tension tend to segregate (Oxygen, Fluorine have the tendency to segregate) and Li segregates in Sn-Li.

Segregation effects the sputter flux composition- Sputtering rate Vs Segregation rate?-At high sputter rates, the effect is transient leading to an equilibrium sputter flux resembling bulk composition.

Sputtering of dynamically evolving surface is challenging and not known.

Also known that the erosion rate at higher temperatures for liquid metals is greater than what can be attributed to the sum of independent sputter and evaporation fluxes- Need explanation!



Oxidation of Sn droplets

TAKAYUKI MIMA, HIRONORI TAKEUCHI, SHIGEO ARAI, KEISUKE KISHITA, KOTARO KURODA, AND HIROYASU SAKA," In Situ Observation of Oxidation of Liquid Droplets of Tin and Melting Behavior of a Tin Particle Covered With a Tin Oxide Layer," MICROSCOPY RESEARCH AND TECHNIQUE 72:223–231 (2009)

In many processes involving real materials, the liquid phase plays a very important role. One of the most typical examples is solidification: many properties of solidified products are determined when materials transform from the liquid phase into the solid phase. To obtain better properties of solid materials, the liquid-to-solid reaction, that is solidification, must be controlled carefully. For this purpose, it is vital to have a detailed knowledge of the structure and behavior of the solid-liquid (S-L) interface.

CONCLUSIONS

- 1. The solid-liquid interface in Sn was atomically rough.
- 2. The contact angle of a solid Sn was larger than 90⁰. This is in sharp disagreement with previous results.
- 3. It was shown that this discrepancy cannot be explained by an increase in the internal pressure of Sn due to the formation of Sn3O4 layer.
- 4. Possible reasons for this discrepancy were discussed in terms of change in various interfacial and/or surface energies due to the presence of oxygen atoms.



Proposed Work – Surface Sciences Group

- Utilize the Scanning Auger Microprobe (SAM) and XPS to characterize the surface of lithiated ATJ graphite.
- Use the chemical shifts in the KVV transition of Li at 39 eV to produce separate maps of Li and LiO.
 - Obtain a clean spectrum of bulk Li
 - Evaporated films
 - Lithium oxide films on graphite, how do they respond to H?
 - Lithium hydride films on graphite, how do they respond to O?







D+

Proposed Work – Surface Science Group

- A differentially pumped ion gun can be used as a source of H+, D+, or O + for ion-induced chemistry studies, and can also produce Ar+ for sputtering applications.
- Determine utility of reflection electron energy-loss spectroscopy (RHEELS) obtained in SAM for detecting and imagine H-rich phases.
- Employ electron stimulated desorption (ESD) of D+ caused by incidient electron beam to obtain additional chemical information.
- Temperature programmed desorption (TPD) can be used to determine energetics of surface processes; H and D concentrations in the Li film and desorbed products of chemical reactions, and the Li adhesion energy.
- Surface science investigations of reactions and processes on sufaces of Li, Ga, Sn and Li+Sn eutectics, using a wide range of ion scattering probes and electron spectroscopy for surface analysis.



Tokamak in-situ diagnosis of PMI: measure dynamic response



NSTX Materials Analysis and Particle Probe (MAPP), with in-vacuo surface analysis. FY2011 and FY2012 NSTX experimental campaigns.





